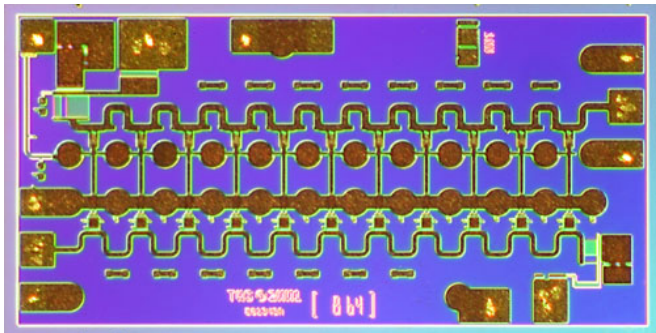


## DC to >50 GHz MPA with AGC



### Description

The TriQuint TGA4803 is a medium power wideband AGC amplifier that typically provides 8dB small signal gain with 3dB AGC range. Typical input and output return loss is >10dB. Typical Noise Figure is 5dB at 3GHz. Typical saturated output power is 17dBm. Small signal 3dB BW is >50GHz. RF ports are DC coupled enabling the user to customize system corner frequencies.

The TGA4803 is an excellent choice for 43Gb/s NRZ applications. The TGA4803 is capable of driving a single Electro-Absorptive optical Modulator (EAM) with electrical Non-Return to Zero (NRZ) data. In addition, the TGA4803 may also be used as a transmit predriver or a receive gain block.

Drain bias may be applied through the output port for best efficiency or through the on-chip drain termination. Three stages in cascade demonstrated 3.8Vpp output voltage swing with 350mV at the input when stimulated with 43Gb/s 2<sup>31</sup>-1prbs NRZ data.

The TGA4803 requires off-chip decoupling and blocking components. Each device is 100% DC and RF tested on-wafer to ensure performance compliance. The device is available in die form.

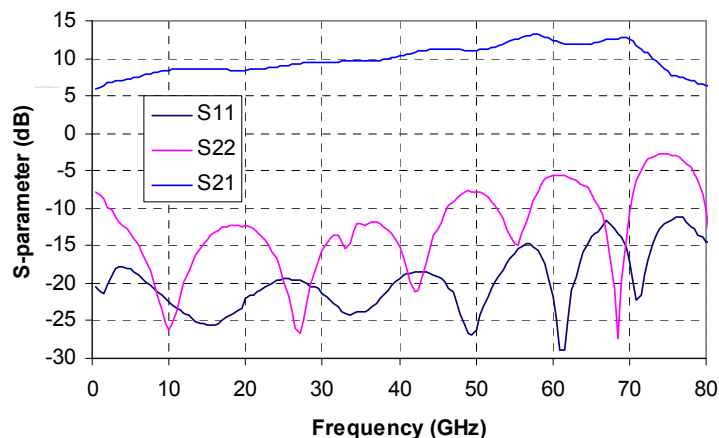
Lead-free and RoHS compliant

### Key Features and Performance

- 0.15um pHEMT Technology
- DC to >50GHz Linear BW
- 8dB Gain, 14dBm @ P1dB
- Group Delay Ripple +/- 6ps to 50 GHz
- <10ps Edge Rates (20/80)
- 3.5Vpp 43Gb/s NRZ PRBS
- Bias: Vd=6.5V, 100mA
- Chip Size: 1.90 x 1.09 x 0.10 mm

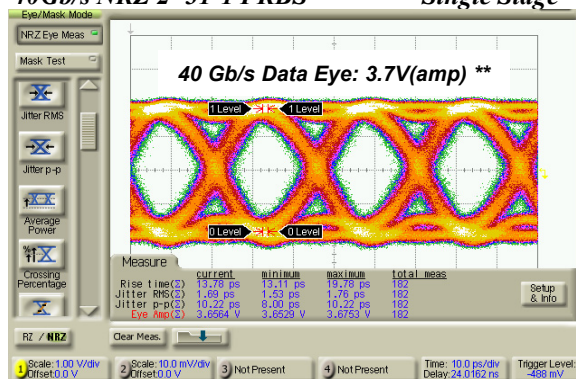
### Primary Applications

- Test Equipment
- Ultra Wideband
- 43Gb/s OC768 EAM Driver
- 43Gb/s OC768 Gain Stage:



40Gb/s NRZ 2<sup>31</sup>-1 PRBS

Single Stage



**\*\* Input 40Gb/s data stream generated using an Anritsu MUX. Vin=1.8Vpp.**

## MAXIMUM RATINGS 7/

SYMBOL	PARAMETER <u>6/</u>	VALUE	NOTES
V <sup>+</sup> Vd(fet)	POSITIVE SUPPLY VOLTAGE		
	Biased thru On-chip Drain Termination	10 V	<u>1/</u>
	Biased thru the RF Output Port using a Bias Tee	8 V	
I <sup>+</sup> Id	POSITIVE SUPPLY CURRENT		<u>1/</u>
	Biased thru On-chip Drain Termination	125 mA	
	Biased thru the RF Output Port using a Bias Tee	125 mA	
P <sub>D</sub>	POWER DISSIPATION	1.5 W	<u>2/</u>
Vg Ig	NEGATIVE GATE		
	Voltage	+1V to -3V	
	Gate Current	5 mA	
Vctl Ictl	CONTROL GATE		
	Voltage	Vd/2 to -3V	<u>3/</u>
	Gate Current	5 mA	
P <sub>IN</sub> Vin	RF INPUT		
	Sinusoidal Continuous Wave Power	18 dBm	
	43Gb/s PRBS Input Voltage Peak to Peak	4 Vpp	
T <sub>CH</sub>	OPERATING CHANNEL TEMPERATURE	200 °C	<u>4/ 5/</u>
	MOUNTING TEMPERATURE (30 SECONDS)	320 °C	
T <sub>STG</sub>	STORAGE TEMPERATURE	-65 to 150 °C	

### Notes:

- 1/ Assure Vd - Vctl <6V. Compute Vd as follows, Vd=V+ - Id\*25.
- 2/ Assure the combination of Vd and Id does not exceed maximum power dissipation rating.
- 3/ When operated at this bias condition with a base plate temperature of 70 °C, the median life is 1.4E4 hours
- 4/ Assure Vctl never exceeds Vd during bias up and down sequences. Also, assure Vctl never exceeds 4V during normal operation.
- 5/ These ratings apply to each individual FET.
- 6/ Junction operating temperature will directly affect the device median time to failure (Tm). For maximum life, it is recommended that junction temperatures be maintained at the lowest possible levels.
- 7/ These ratings represent the maximum operable values for the device.

RF SPECIFICATIONS  
 (T<sub>A</sub> = 25°C ± 5°C)

NOTE	TEST	MEASUREMENT CONDITIONS	VALUE			UNITS
			MIN	TYP	MAX	
	SMALL SIGNAL BW			>50		GHz
<u>1/</u>	SMALL-SIGNAL GAIN MAGNITUDE	2.5GHz		8		dB
	AGC RANGE	Midband		3		dB
	NOISE FIGURE	14 GHz		6		dB
	SATURATED OUTPUT VOLTAGE (EYE AMPLITUDE)	43Gb/s with Vin=2Vpp		3.5		V
<u>1/</u>	P1dB	DC-20GHz		TBD		dBm
<u>1/</u>	INPUT RETURN LOSS MAGNITUDE	DC-50GHz		-10		dB
<u>1/</u>	OUTPUT RETURN LOSS MAGNITUDE	DC-50GHz		-10		dB
	GROUP DELAY	DC-50GHz		+/- 20		ps
	RISE TIME	20/80%		10		ps

## Notes:

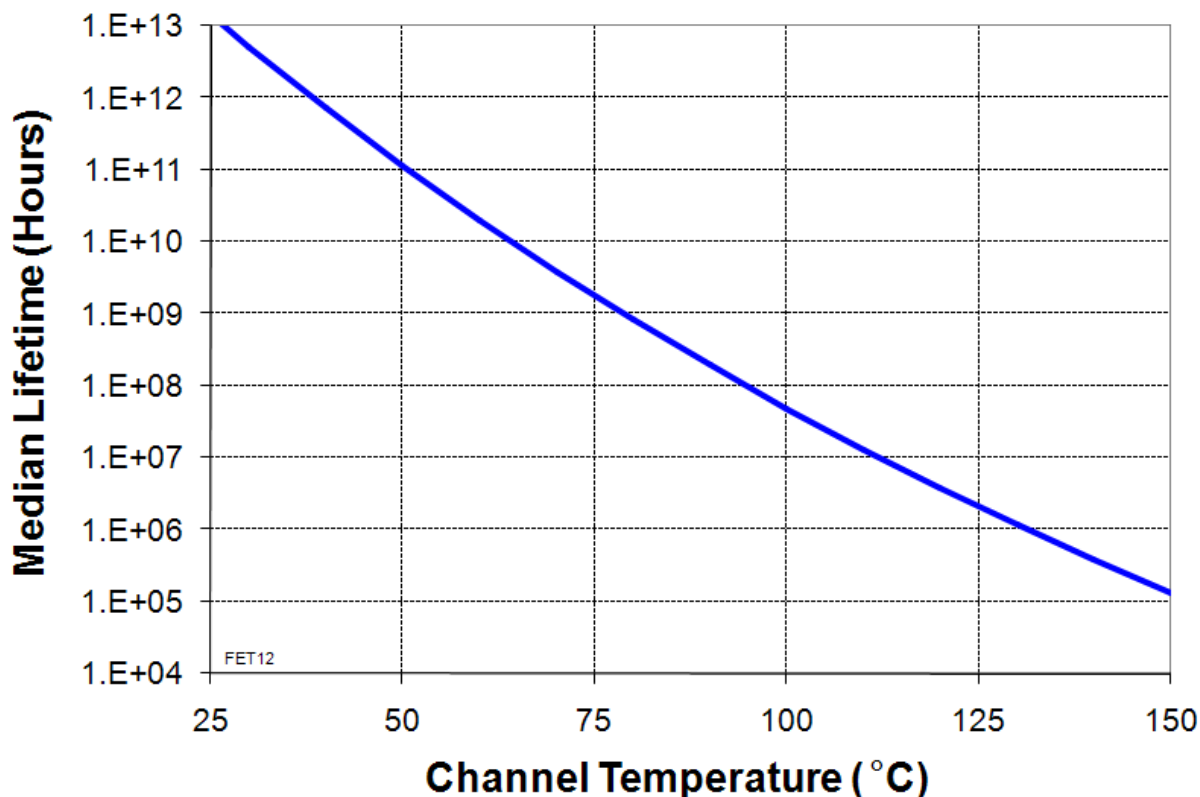
1/ Verified at RF on-wafer probe.

THERMAL INFORMATION

Parameter	Test Condition	$T_{CH}$ (°C)	$\theta_{JC}$ (°C/W)	$T_m$ (HRS)
$\theta_{JC}$ Thermal Resistance (channel to backside of carrier)	$V_d = 6V$ , $V_{ctrl} = 3V$ , $I_D = 100mA$	109	65	2.3E6

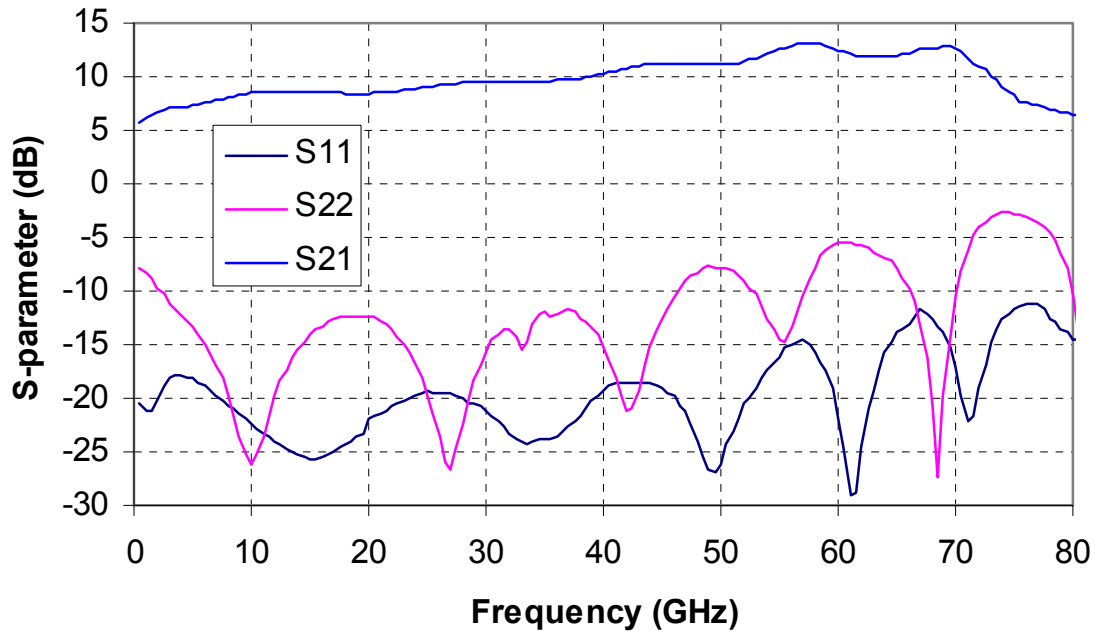
Note: Assumes eutectic attach using 1.5 mil 80/20 AuSn mounted to a 20 mil CuMo Carrier at 70°C baseplate temperature. Worst case condition with no RF applied, 100% of DC power is dissipated.

**Median Lifetime ( $T_m$ ) vs. Channel Temperature**

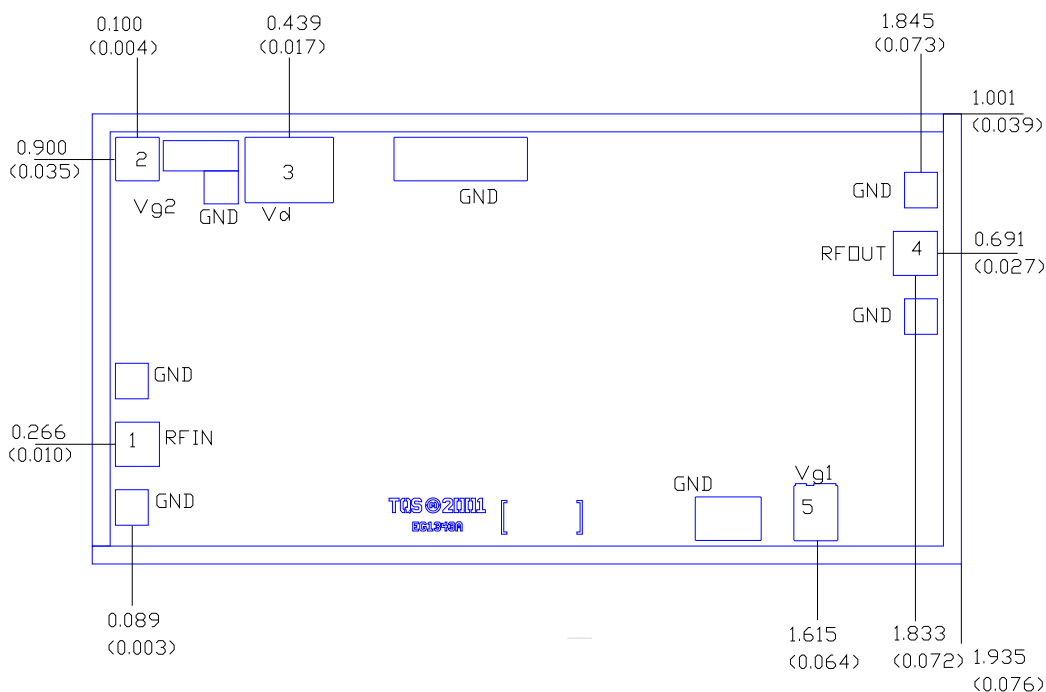


### Measured Performance

Bias Conditions:  $V_d = 10\text{ V}$ ,  $I_{dq} = 82\text{ mA}$ ,  $V_{g2} = 3\text{--}3.2\text{ V}$   
@ Room Temperature



## Mechanical Drawing



Units: millimeters (inches)

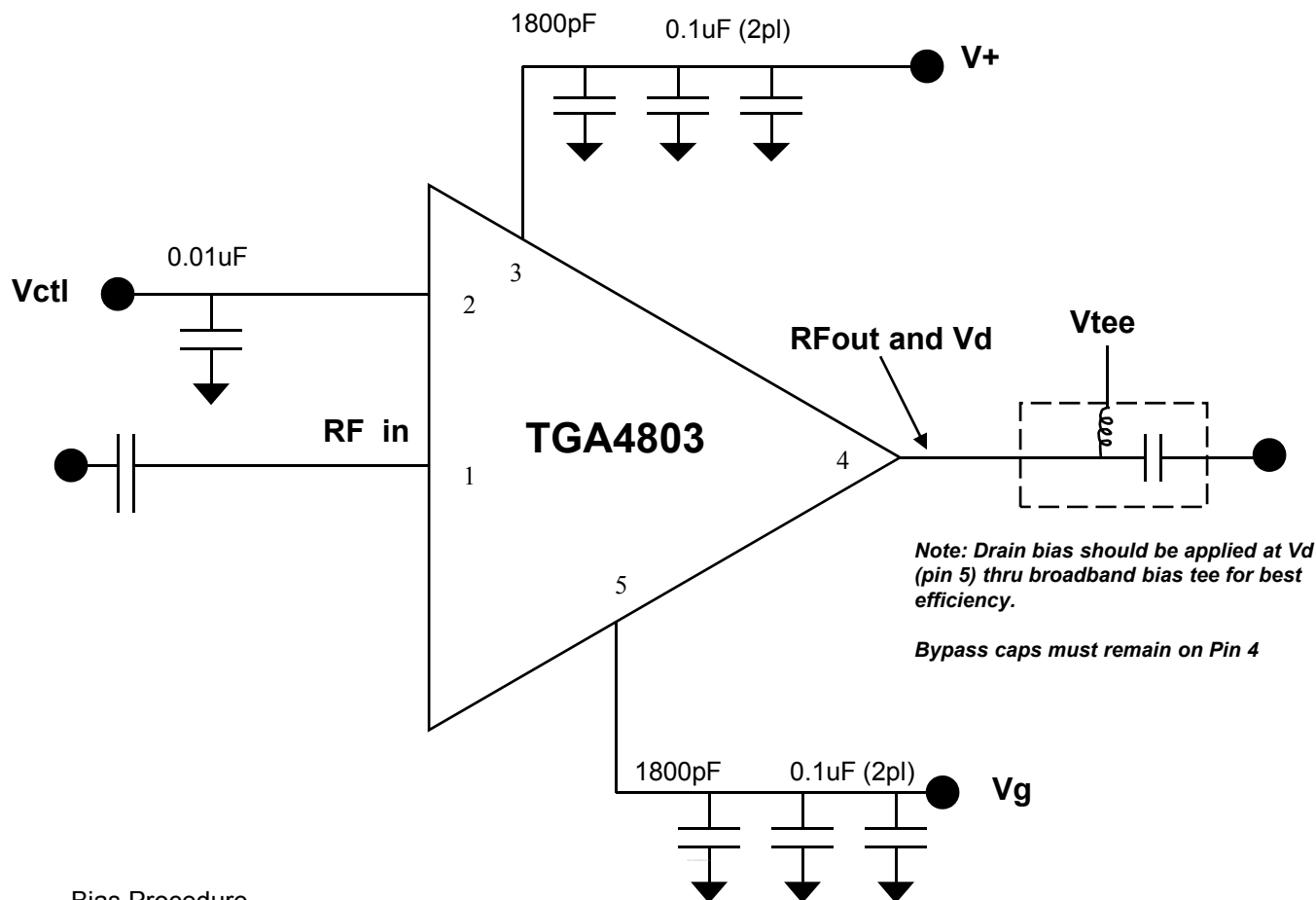
Thickness: 0.100 (0.004)

Chip edge to bond pad dimensions are shown to center of bond pad

Chip size tolerance: +/-0.051 (0.002)

GND is back of MMIC

Bond pad #1	RFIN	0.098x0.098 (0.004x0.004)
Bond pad #2	Vg2	0.097x0.097 (0.004x0.004)
Bond pad #4	RFOUT	0.098x0.098 (0.004x0.004)
Bond pad #3	Vd	0.197x0.145 (0.008x0.006)
Bond pad #5	Vg1	0.098x0.123 (0.004x0.005)



#### Bias Procedure

##### A. For applying drain bias thru Vd

1. Make sure no RF power is applied to the device before continuing.
2. Set  $V_g=0$  Set  $V_{ctl}=0$ .
3. Raise  $V_d$  to 6V while monitoring drain current.  $I_d$  should be near 20mA.
4. Raise  $V_{ctl}$  to +2.5V (no greater than 3.5V).
5. Adjust  $V_g$  more positive until drain current reaches 100mA.
6. Apply  $V_{in}=1.8V$ (amplitude) NRZ 40Gb/s

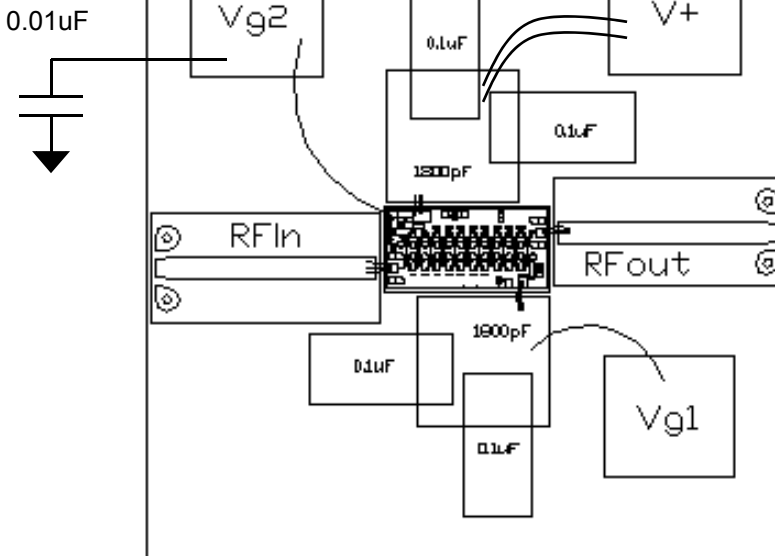
##### B. For applying drain bias thru V+

1. Make sure no RF power is applied to the device before continuing.
2. Set  $V_g=0$  Set  $V_{ctl}=0$ .
3. Raise  $V_+$  to 5V while monitoring drain current.  $I_+$  should be near 20mA.
4. Raise  $V_{ctl}$  to 2.5V (no greater than 3.5V)
5. Raise  $V_g$  more positive until drain current is 80mA
6. Raise  $V_+$  to 8V
7. Adjust  $V_g$  for  $I_d=100mA$
8. Apply  $V_{in}=1.8V$ (amplitude) NRZ 40Gb/s

#### CAUTION:

1. Assure  $V_d - V_{ctl} < 6V$ . When biasing thru  $V_+$ , compute  $V_d$  as follows,  $V_d = V_+ - I_d \cdot 30$ .
2. Assure  $V_{ctl}$  never exceeds  $V_d$  during bias up and down sequences. Also, assure  $V_{ctl}$  never exceeds 4V during normal operation.

Recommend additional  
0.01uF bypass cap  
located on Vctrl supply line  
on test fixture



#### Reflow process assembly notes:

- AuSn (80/20) solder with limited exposure to temperatures at or above 300°C
- alloy station or conveyor furnace with reducing atmosphere
- no fluxes should be utilized
- coefficient of thermal expansion matching is critical for long-term reliability
- storage in dry nitrogen atmosphere

#### Component placement and adhesive attachment assembly notes:

- vacuum pencils and/or vacuum collets preferred method of pick up
- avoidance of air bridges during placement
- force impact critical during auto placement
- organic attachment can be used in low-power applications
- curing should be done in a convection oven; proper exhaust is a safety concern
- microwave or radiant curing should not be used because of differential heating
- coefficient of thermal expansion matching is critical

#### Interconnect process assembly notes:

- thermosonic ball bonding is the preferred interconnect technique
- force, time, and ultrasonics are critical parameters
- aluminum wire should not be used
- discrete FET devices with small pad sizes should be bonded with 0.0007-inch wire
- maximum stage temperature: 200°C

***GaAs MMIC devices are susceptible to damage from Electrostatic Discharge. Proper precautions should be observed during handling, assembly and test.***



## **Assembly Process Notes**

Reflow process assembly notes:

- Use AuSn (80/20) solder with limited exposure to temperatures at or above 300<sup>0</sup>C (30 seconds max).
- An alloy station or conveyor furnace with reducing atmosphere should be used.
- No fluxes should be utilized.
- Coefficient of thermal expansion matching is critical for long-term reliability.
- Devices must be stored in a dry nitrogen atmosphere.

Component placement and adhesive attachment assembly notes:

- Vacuum pencils and/or vacuum collets are the preferred method of pick up.
- Air bridges must be avoided during placement.
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